

IN THE ABSTRACT

Please amend the abstract appearing at page 40, lines 2-21, as follows:

In an electron beam apparatus including an electron source and an electron beam irradiation member, a potential specifying plate including openings through which an electron transmits is provided between the electron source and the electron beam irradiation member. A spacer is located between the electron beam irradiation member and the potential specifying plate. In the case where a distance between a region between one ~~[[of the openings]]~~ opening of the potential specifying plate ~~[[which is]]~~ near the spacer and the spacer and the electron beam irradiation member is ~~[[given by]]~~ $D1$ and a distance between a region between ~~[[the one]]~~ that opening ~~of the potential specifying plate which is near the spacer~~ and another opening ~~[[thereof which is]]~~ not near the spacer and the electron beam irradiation member is given by $D2$, if $D1 < D2$ is satisfied, a deviation of an orbit of an electron beam emitted from the electron source is suppressed, so that it is possible to produce a high quality image.